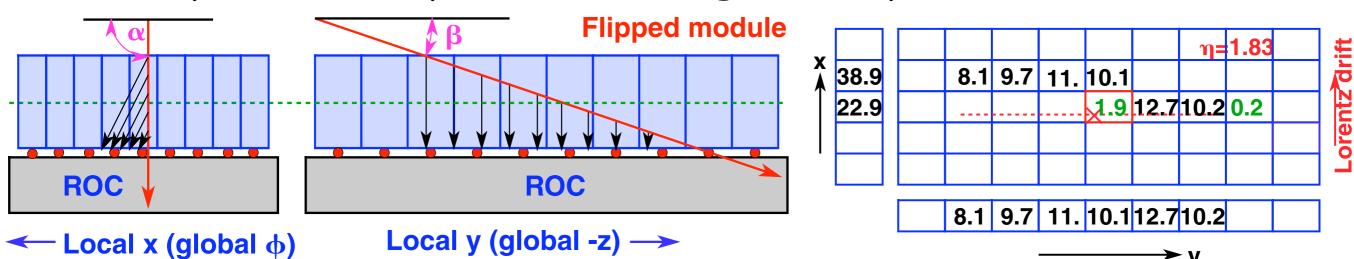
Calibration of Radiation Damage: Effects on Pixel Reconstruction

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Hit Reconstruction

Tracks deposit distinct patterns of charge on the pixel sensors



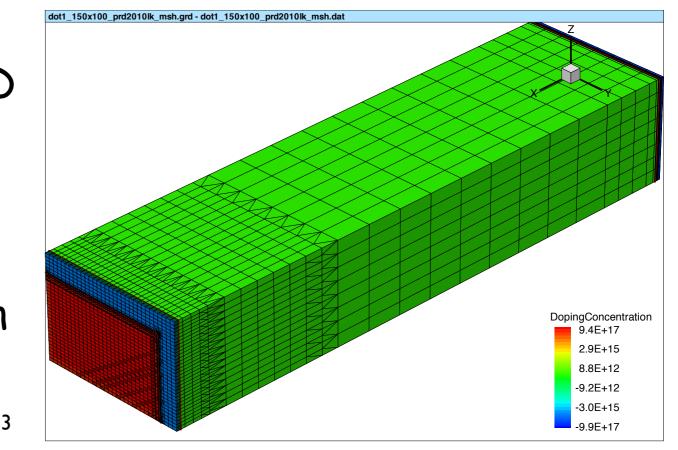
- Hit position estimation is based on 1D projections of the 2D cluster
 - factorizes due to field configurations and cell periodicity
 - projected shapes depend upon the projected angles α and β
 - * reconstruction algorithms use angle information iteratively
- Two techniques used in track reconstruction
 - "Generic" technique is n-like, uses end pixel charges of projection
 * faster, less precise algorithm used for all but last tracking pass
 * needs external Lorentz drift calibration
 - "Template" technique fits projections to simulated profiles
 - * slower, more precise algorithm used for final fitting pass
 - * needs full cluster shape calibration
 - * generates probabilities that test the consistency of the shapes

Pixelav Detailed Simulation

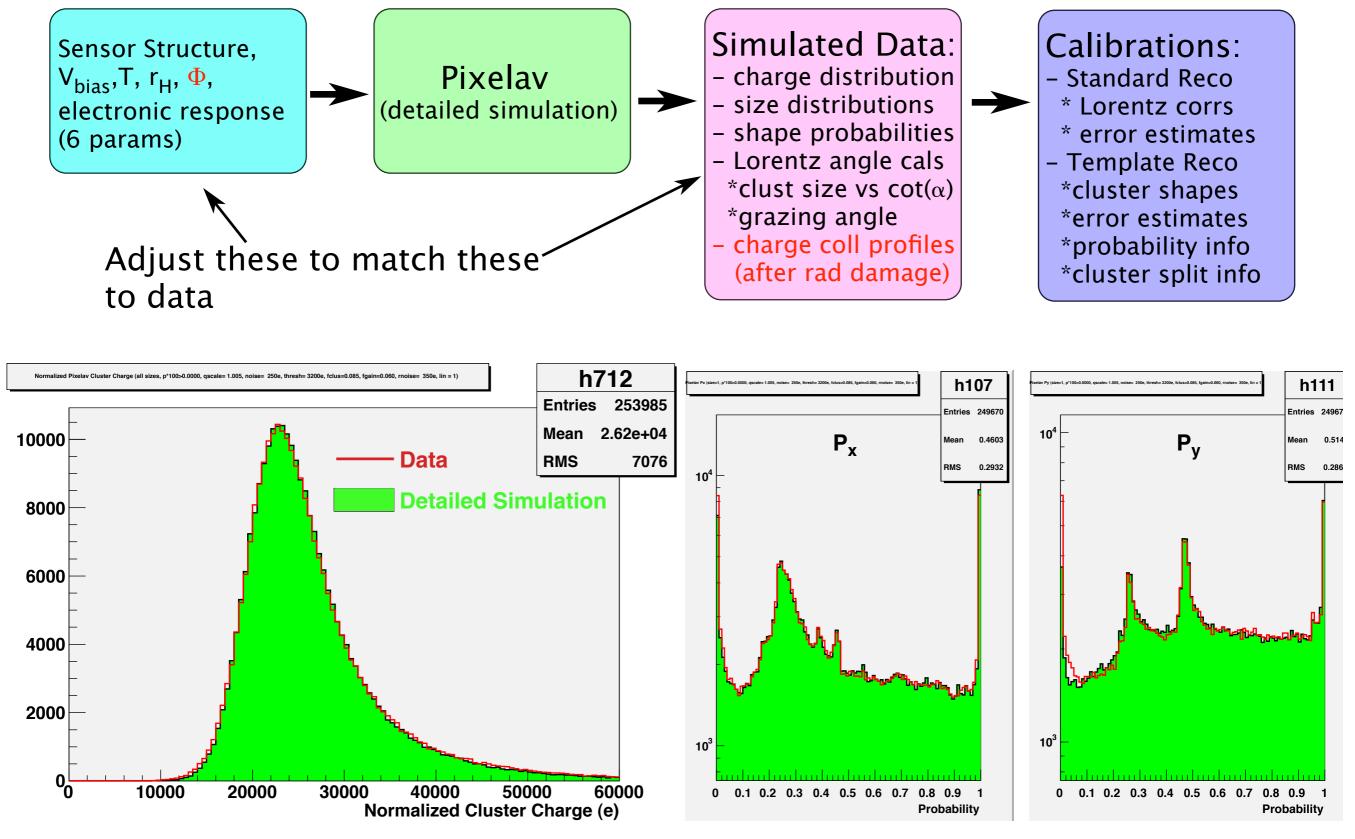
- Created to interpret beam tests of irradiated sensors, now used to perform Lorentz calibrations and generate template profile shapes:
- Charge deposition model based on Bichsel π -Si x-sections
 - delta ray range: Continuous Slowing Down Approx + Nist Estar dedx
 - plural scattering and magnetic curvature of delta ray tracks
- Carrier transport from Runge-Kutta integration of saturated drift

$$\frac{d\vec{x}}{dt} = \vec{v} = \frac{\mu \left[q\vec{E} + \mu r_H \vec{E} \times \vec{B} + q\mu^2 r_H^2 (\vec{E} \cdot \vec{B}) \vec{B} \right]}{1 + \mu^2 r_H^2 |\vec{B}|^2}$$

- electric field map from ISE TCAD simulation of pixel cell
- includes diffusion, trapping, and charge induction on implants
- Electronic Simulation: noise, linearity, thresholds, mis-calibration



Calibration of Reconstruction Algs



Modeling of Irradiated Sensors

Space charge in irradiated sensors can be produced by ionized traps. The Shockley-Read-Hall (SRH) description is based on ALL trapping states:

$$\rho_{\text{eff}} = e \sum_{D} N_D f_D - e \sum_{A} N_A f_A + \rho_{\text{dopants}}$$
$$\simeq e \left[N_D f_D - N_A f_A \right] + \rho_{\text{dopants}}$$

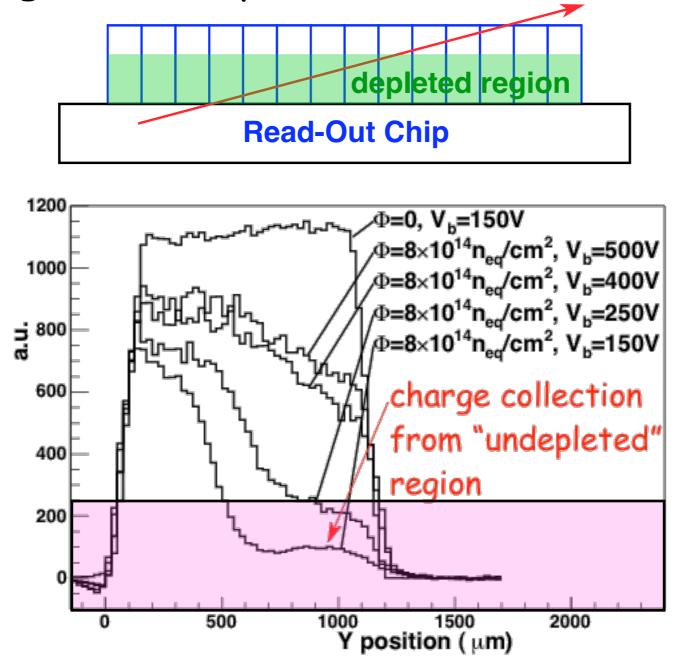
 N_D and N_A are the densities of h- and e-traps

 f_D and f_A are the trap occupation probabilities

- follow Eremin, Verbitskaya, Li (EVL): use single h/e-traps to model E-field
 - D and A states don't have to be physical states: they represent average quantities!
 - model parameters are not physical
- e/h trapping is modeled independently in Pixelav using measured trapping rates to relate them the fluence Φ

Tuning the Simulation

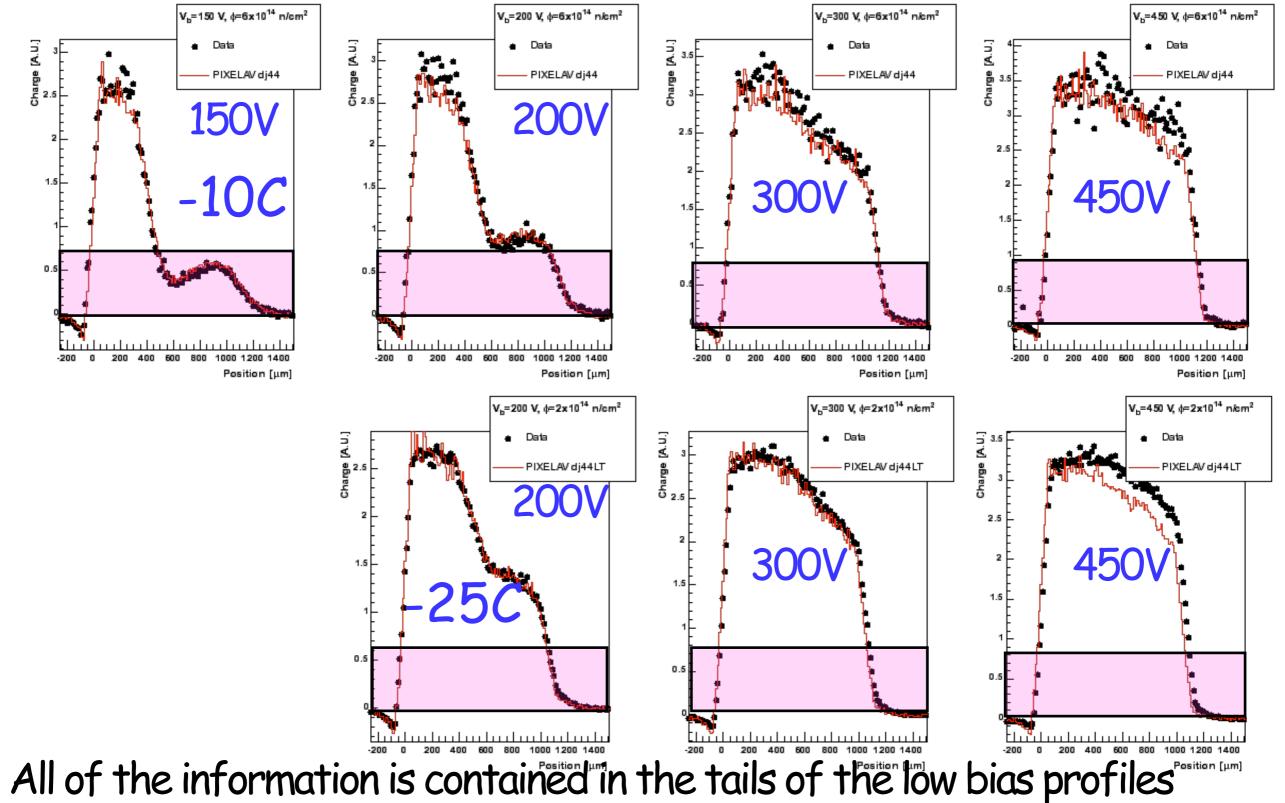
Compare the charge collection profiles of real and simulated data



• Our test beam experience was based upon reading all pixels (no threshold)

in CMS, we will not see the smallest ~25% of the signals

Successful tuning of sensor at $\Phi_1=5.9\times10^{14}$ nea/cm²



- the "feature" corresponding to the field minimum is observable at some V and T!

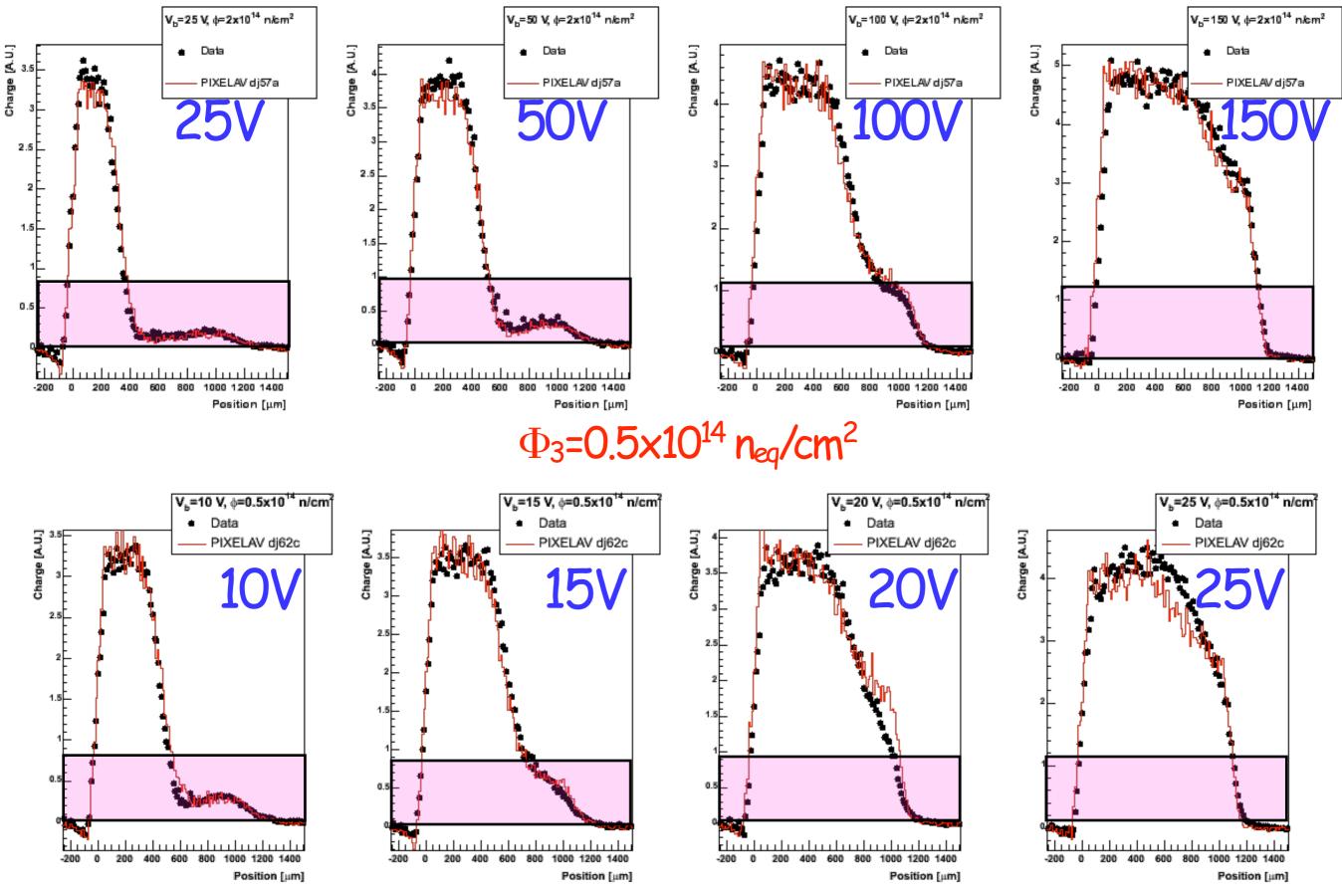
Scale to lower fluences using an empirical set of relationships

 $\Gamma_{e/h}(\Phi_2) = R_{\Gamma} \cdot \Gamma_{e/h}(\Phi_1)$ $N_A(\Phi_2) = R_A \cdot N_A(\Phi_1)$ $N_D(\Phi_2) = R_D \cdot N_D(\Phi_1)$

 $R_{\Gamma} = \Phi_2 / \Phi_1$ $R_A = R_{\Gamma} (1 + \delta)$ $R_D = R_{\Gamma} (1 - \delta)$

- Trapping rates are linear in the fluence (observed from direct measurements)
- Scale donor and acceptor densities to keep the average factor equal to the ratio of fluences
 - keeps leakage current approximately linear in fluence (also well established)
 - allows the ratio N_A/N_D to vary with fluence

Φ_2 =2.0x10¹⁴ n_{eq}/cm²



Scale factor summary:

- igstarrow trapping rates are linear in Φ

The good news:

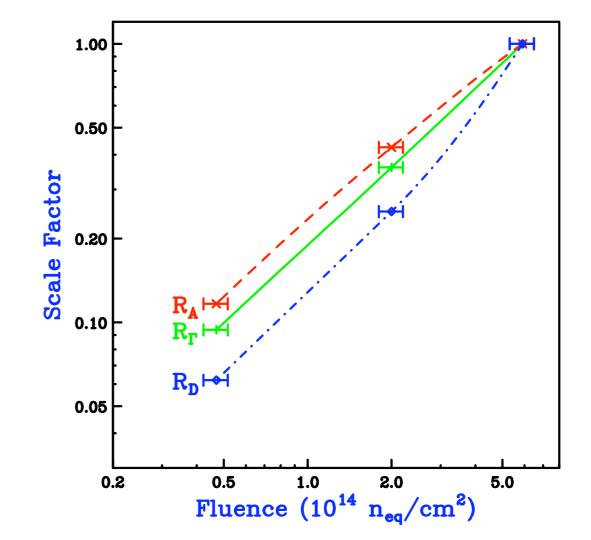
 $\mbox{ }$ We have a good understanding of the Φ dependence of the sensor response

- depends upon only 1 parameter (Φ) modulo annealing effects

The bad news:

ROC readout thresholds will limit ability to see the profile tails

- need voltage points near transition to backside charge collection
- Poorer resolution of track entry point into sensor than test beam



Expected Effect of Fluence Calibrations

Use tuned simulation to predict performance after damage: with and without calibration

Fluence Φ	Bias	x Bias	x Res (rms)	x Pull (rms)	y Bias	y Res (rms)	y Pull (rms)
0	150V	-0.6 μm	<mark>Ι6.3</mark> μm	1.00	0.1 μm	25.1 μm	1.02
$2 \times 10^{14} n_{eq}/cm^2$ (no cal)	200V	<mark>-12.4</mark> μm	I7.0 μm	1.80	-0.1 μm	34.0 μm	1.51
$2 \times 10^{14} n_{eq}/cm^2(w/cal)$	200V	<mark>0.8</mark> μm	I7.Iμm	0.94	0.0 μm	29.2 μm	0.98
$6 \times 10^{14} n_{eq}/cm^2$ (no cal)	400V	-22.0 µm	I7.4μm	1.91	0.1 μm	35.1 μm	1.64
$6 \times 10^{14} n_{eq}/cm^{2}(w/ cal)$	400V	Ι.0 μm	I7.I μm	0.93	0.1 μm	30.6 μm	1.00

Generic Algorithm (Barrel)

Template Algorithm (Barrel)

Fluence Φ	Bias	x Bias	x Res (rms)	x Pull (rms)	y Bias	y Res (rms)	y Pull (rms)
0	150V	-0.3µm	<mark>Ι 2.0</mark> μm	1.06	0.1 μm	23.0 μm	1.06
$2 \times 10^{14} n_{eq}/cm^2$ (no cal)	200V	-13.5μm	I 5. I μm	2.13	-0.1 μm	34.0 μm	1.66
$2 \times 10^{14} n_{eq}/cm^{2}(w/cal)$	200V	<mark>0.3</mark> μm	Ι 3.2 μm	1.00	0.0 μm	27.2 μm	1.01
$6 \times 10^{14} n_{eq}/cm^2$ (no cal)	400V	<mark>-22.3</mark> µm	<mark>I 5.6</mark> µm	2.30	0.1 μm	34.4 μm	1.79
$6 \times 10^{14} n_{eq}/cm^2(w/cal)$	400V	<mark>0.3</mark> μm	I4.7μm	0.98	0.1 μm	29.0 μm	1.01

Summary

- Bias scans are essential to tune the radiation damage parameters
 - measure charge profiles at a sequence of voltages
 - readout thresholds will hide interesting features
 - * may need fairly fine scan in voltage to see them
 - * can guess voltages from information already available
- Tuned radiation damage simulation is needed even to interpret Lorentz calibrations
 - already have a ~10% correction to account for implant focusing
 - trapping and charge induction change everything even more: can get large offsets
- Tuned simulation is essential to keep the template reco working
 - resolution is improved, biases eliminated
- Tuned simulation is essential to keep error estimates accurate
 - existing error calibration would produce large pulls in both techniques
 - * tracking and b-tagging would be significantly impacted